

L Number	Hits	Search Text	DB	Time stamp
1	9	((("5308447") or ("4675530") or ("5475319") or ("6232134") or ("5474877") or ("5721090") or ("5587587") or ("6458704") or ("6162565"))).PN.	USPAT; US-PGPUB	2003/12/30 09:30
2	2855	electrostatic near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)	USPAT; US-PGPUB	2003/12/30 10:01
3	438	(electrostatic near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) and wafer	USPAT; US-PGPUB	2003/12/30 09:31
4	131	((electrostatic near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) and wafer) and solution	USPAT; US-PGPUB	2003/12/30 09:31
5	26	((electrostatic near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) and wafer) and dispens\$2	USPAT; US-PGPUB	2003/12/30 09:34
6	2711	electrostatic near2 chuck	USPAT; US-PGPUB	2003/12/30 09:41
7	154	(electrostatic near2 chuck) and dispens\$2	USPAT; US-PGPUB	2003/12/30 09:38
8	3959	static near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)	USPAT; US-PGPUB	2003/12/30 09:38
9	0	((electrostatic near2 chuck) and dispens\$2) and (static near2 (sens\$2 detect\$3 monitor\$2 regulat\$3))	USPAT; US-PGPUB	2003/12/30 09:35
10	127	((electrostatic near2 chuck) and dispens\$2) and (sens\$2 detect\$3 monitor\$2 regulat\$3)	USPAT; US-PGPUB	2003/12/30 09:35
11	7813	wafer near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)	USPAT; US-PGPUB	2003/12/30 09:38
12	368	(wafer near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) and dispens\$2	USPAT; US-PGPUB	2003/12/30 09:38
13	7	(electrostatic near2 chuck) and ((wafer near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) and dispens\$2)	USPAT; US-PGPUB	2003/12/30 09:38
14	51	electrostatic and ((wafer near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) and dispens\$2)	USPAT; US-PGPUB	2003/12/30 09:43
15	341	(electrostatic near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) same (wafer substrate plasma)	USPAT; US-PGPUB	2003/12/30 09:43
16	65	(electrostatic near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) near3 (wafer substrate plasma)	USPAT; US-PGPUB	2003/12/30 09:45
17	6933	dispens\$2 near2 control\$3	USPAT; US-PGPUB	2003/12/30 09:46
18	0	((electrostatic near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) same (wafer substrate plasma)) and (dispens\$2 near2 control\$3)	USPAT; US-PGPUB	2003/12/30 09:46
19	1067	dispens\$2 near2 controller	USPAT; US-PGPUB	2003/12/30 09:46
20	0	((electrostatic near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) same (wafer substrate plasma)) and (dispens\$2 near2 controller)	USPAT; US-PGPUB	2003/12/30 09:46
21	10	((electrostatic near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) same (wafer substrate plasma)) and dispens\$2	USPAT; US-PGPUB	2003/12/30 09:49
22	21038	charge near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)	USPAT; US-PGPUB	2003/12/30 09:49
23	1886	(charge near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) and wafer	USPAT; US-PGPUB	2003/12/30 10:01
24	135	((charge near2 (sens\$2 detect\$3 monitor\$2 regulat\$3)) and wafer) and dispens\$2	USPAT; US-PGPUB	2003/12/30 10:01
25	2737	electrostatic near2 (sens\$2 detect\$3 monitor\$2)	USPAT; US-PGPUB	2003/12/30 10:01
26	306	(electrostatic near2 (sens\$2 detect\$3 monitor\$2)) same (wafer substrate)	USPAT; US-PGPUB	2003/12/30 10:13
27	10	((electrostatic near2 (sens\$2 detect\$3 monitor\$2)) same (wafer substrate)) and dispens\$2	USPAT; US-PGPUB	2003/12/30 10:01

28	3	("4564280" "5487398" "5555234").PN.	USPAT	2003/12/30 10:06
29	10	5854953.URPN.	USPAT	2003/12/30 10:07
30	5	("4396705" "5762749" "5854953" "5887605" "6334902").PN.	USPAT	2003/12/30 10:09
31	57	(electrostatic near2 (sens\$2 detect\$3 monitor\$2)) near3 (wafer substrate)	USPAT;	2003/12/30 10:15
32	4957	control\$2 near2 dispensing	US-PGPUB	2003/12/30 10:16
33	13	(electrostatic near2 (sens\$2 detect\$3 monitor\$2)) and (control\$2 near2 dispensing)	USPAT;	2003/12/30 10:25
34	11952	reduc\$2 near2 charge	US-PGPUB	2003/12/30 10:33
35	5383	(reduc\$2 near2 charge) and (wafer substrate)	USPAT;	2003/12/30 10:45
36	5	(control\$2 near2 dispensing) and ((reduc\$2 near2 charge) and (wafer substrate))	US-PGPUB	2003/12/30 10:26
37	10007	sens\$3 near2 charge	USPAT;	2003/12/30 10:47
38	952	(sens\$3 near2 charge) same (wafer substrate workpiece)	US-PGPUB	2003/12/30 10:34
39	38	((sens\$3 near2 charge) same (wafer substrate workpiece)) and dispensing	USPAT;	2003/12/30 10:44
40	27	((sens\$3 near2 charge) same (wafer substrate workpiece)) and dispenser	US-PGPUB	2003/12/30 10:38
41	532	dispensing near2 controller	USPAT;	2003/12/30 10:45
42	115	(dispensing near2 controller) and (wafer substrate)	US-PGPUB	2003/12/30 11:05
43	8	(sens\$3 near2 charge) and ((dispensing near2 controller) and (wafer substrate))	USPAT;	2003/12/30 10:48
44	25147	(detect\$3 sens\$3 measur\$2) near2 charge	US-PGPUB	2003/12/30 11:04
45	10007	(sens\$3 near2 charge) and ((detect\$3 sens\$3 measur\$2) near2 charge)	USPAT;	2003/12/30 10:49
46	9	((dispensing near2 controller) and (wafer substrate)) and ((detect\$3 sens\$3 measur\$2) near2 charge)	US-PGPUB	2003/12/30 10:49
47	13	(dispensing near2 controller) and ((detect\$3 sens\$3 measur\$2) near2 charge)	USPAT;	2003/12/30 10:51
48	1088	photoresist and ((detect\$3 sens\$3 measur\$2) near2 charge)	US-PGPUB	2003/12/30 10:51
49	43	(photoresist and ((detect\$3 sens\$3 measur\$2) near2 charge)) and dispenser	USPAT;	2003/12/30 11:05
50	116516	(detect\$3 sens\$3 measur\$2) near2 voltage	US-PGPUB	2003/12/30 11:06
51	96	((detect\$3 sens\$3 measur\$2) near2 voltage) near2 wafer	USPAT;	2003/12/30 11:04
52	26955	((detect\$3 sens\$3 measur\$2) near2 voltage) and (wafer substrate)	US-PGPUB	2003/12/30 11:05
53	4613	((detect\$3 sens\$3 measur\$2) near2 voltage) same (wafer substrate)	USPAT;	2003/12/30 11:05
54	579	((detect\$3 sens\$3 measur\$2) near2 voltage) near3 (wafer substrate)	US-PGPUB	2003/12/30 11:06
55	6	((detect\$3 sens\$3 measur\$2) near2 voltage) near3 (wafer substrate)) and dispenser	USPAT;	2003/12/30 11:06
56	12081	(detect\$3 sens\$3 measur\$2) near2 ion	US-PGPUB	2003/12/30 11:06
57	220	((detect\$3 sens\$3 measur\$2) near2 ion) near3 (wafer substrate)	USPAT;	2003/12/30 11:08
58	2	((detect\$3 sens\$3 measur\$2) near2 ion) near3 (wafer substrate)) and dispenser	US-PGPUB	2003/12/30 11:09
59	8	("4312935" "4610953" "5019485" "5144833" "5178989" "5701013" "5702566" "5858879").PN.	USPAT	2003/12/30 11:07
60	0	6479820.URPN.	USPAT	2003/12/30 11:08
61	3482	charge near2 accumul\$3 same (wafer substrate)	US-PGPUB	2003/12/30 14:01
62	63	(charge near2 accumul\$3 same (wafer substrate)) and dispenser	USPAT;	2003/12/30 11:16
			US-PGPUB	

63	654	(charge near2 accumulat\$3 same (wafer substrate)) and photoresist	USPAT; US-PGPUB	2003/12/30 12:36
64	8	((charge near2 accumulat\$3 same (wafer substrate)) and photoresist) and dispenser	USPAT; US-PGPUB	2003/12/30 12:25
65	44	((charge near2 accumulat\$3 same (wafer substrate)) and photoresist) and dispens\$3	USPAT; US-PGPUB	2003/12/30 12:29
66	737	(charge near2 accumulat\$3 same (wafer substrate)) and resist	USPAT; US-PGPUB	2003/12/30 12:29
67	93	((charge near2 accumulat\$3 same (wafer substrate)) and resist) and dispens\$3	USPAT; US-PGPUB	2003/12/30 12:29
68	1	(charge near2 accumulat\$3 same (wafer substrate)) and rinsing near2 liquid	USPAT; US-PGPUB	2003/12/30 12:38
69	61	(charge near2 accumulat\$3 same (wafer substrate)) and rinsing	USPAT; US-PGPUB	2003/12/30 14:00
70	3	("4110810" "4642728" "5057966").PN.	USPAT	2003/12/30 12:42
71	0	6507474.URPN.	USPAT	2003/12/30 12:46
72	14	("4778536" "4827371" "5037506" "5346586" "5356478" "5423944" "5486267" "5712198" "5753137" "5763016" "5849639" "5944907" "5981960" "6024887").PN.	USPAT	2003/12/30 12:49
73	11	("3652331" "4104086" "4149905" "4409260" "4526624" "4668337" "4894353" "4901133" "5108543" "5459105" "5531857").PN.	USPAT	2003/12/30 13:10
75	14	("3873209" "3995216" "4322979" "4464627" "4490618" "4681451" "4827212" "4865453" "5028132" "5091691" "5125740" "5225690" "5233291" "5239183").PN.	USPAT	2003/12/30 13:35
76	7	("4083254" "4322979" "4681451" "4891584" "4941753" "4992728" "5065103").PN.	USPAT	2003/12/30 13:40
77	11	5233291.URPN.	USPAT	2003/12/30 13:43
78	8	("4498043" "4769919" "5036271" "5140272" "5225690" "5233291" "6037781" "6075375").PN.	USPAT	2003/12/30 13:48
79	1	6150832.URPN.	USPAT	2003/12/30 13:50
80	9290	charge near2 (meter\$2 measur\$3)	USPAT; US-PGPUB	2003/12/30 14:00
81	217	(charge near2 (meter\$2 measur\$3)) and rinsing	USPAT; US-PGPUB	2003/12/30 14:00
82	124	((charge near2 (meter\$2 measur\$3)) and rinsing) and (wafer substrate)	USPAT; US-PGPUB	2003/12/30 14:07
83	437	361/226-228.ccls.	USPAT; US-PGPUB	2003/12/30 14:13
84	17	(charge near2 (meter\$2 measur\$3)) and 361/226-228.ccls.	USPAT; US-PGPUB	2003/12/30 14:14
85	1636	361/230-234.ccls.	USPAT; US-PGPUB	2003/12/30 14:14
86	36	(charge near2 (meter\$2 measur\$3)) and 361/230-234.ccls.	USPAT; US-PGPUB	2003/12/30 14:16